

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	673	("xeF.sub.2" or "xenon difluoride") and vapor\$3 and etch\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/12 10:28
L3	328	2 and sacrificial	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/12 09:15
L4	130	("xeF.sub.2" or "xenon difluoride") and vapor\$3 and etch\$3 and "flow rate"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/12 09:56
L5	28325	("xeF.sub.2" or "xenon difluoride" or HF or hydrofluoric) and vapor\$3 and etch\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/12 10:29
L6	4502	("xeF.sub.2" or "xenon difluoride" or HF or hydrofluoric) same vapor\$3 same etch\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/12 10:29
L7	409	("xeF.sub.2" or "xenon difluoride" or HF or hydrofluoric) same vapor\$3 same etch\$3 same sacrificial	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/12 11:07
L8	355	("xeF.sub.2" or "xenon difluoride" or HF or hydrofluoric) same vapor\$3 same "flow rate"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/12 11:07